# Nanyang Technological University School of Electrical & Electronic Engineering

### Nanyang NanoFabrication Centre (N2FC)

Block S1, Level B5, Rm. S1-B5a-01, Nanyang Avenue, Singapore 639798 Tel: (65) 6790-6902/03(N2FC CR1), 6790 6541 (N2FC CR2)

Mask Making Specification Form	IUS-No.
Internal User Submission (For NTU user only)	

Email: n2fc@ntu.edu.sg

#### 1. General Information

Requester Name:			School/Divisio	n :		
Employee ID /Student No:			Laboratory:			
			Email:			
<b>Project Supervisor</b>	(If requ	ester is student)	School/Divisio	n :		
Name:			Work Approved by Project Supervisor			
Email:			Signature :			
Job Submission (N	Note: Lo	ead-time/mask is 2-3 v	weeks on receiv	ving completed charge form)		
Submitted			Received by N2FC staff:			
Name in Full						
Signature						
Date						

### 2. Photo-Mask making information (Please tick or fill in accordingly in the followings.)

<b>Device Title:</b>						
Type of order	New order		Repeated Order			
(please tick one)						
Data File name:						
Data Format:	GDS	CIF		other, please specify		
(please tick one)						
Type of Mask	1X	1X Master		5X		
(please tick one)						
Number of Layers:						
Minimum Feature	Dimension (µm)		@ Layer No./Name			
of Design*:						

Ref : N2FC/Mask Making Spec Form Last Update : 16 Aug 2019

N2FC guarantee the minimum dimension and tolerance of 2.0 +/- 0.3μm. Any feature smaller than this value may not be printed correctly. Please contact N2FC if you want to have better results.

### 3. Data Information (Please tick or fill in accordingly in the followings)

Layout datafile is for :	Select one				
- Complete array of mask data					
- Single die (for Array Stepping Arrangement, refer to Item 7)					
Please indicate the window coordinates in your layout datafile which includes your design (Note: N <sup>2</sup> FC will ignore any data outside the rectangular coordinates)					
Window Coordinates	Lower-Left (LL) corner	Upper-Right (UR) corner			
(X, Y)					

### 4. Mask Substrate Information (Please select the type of mask substrate for your job)

S/N	Type of Substrate	Please select one
1	7"x 7" x 0.12" Soda Lime Glass Mask, flatness <15μm	
2	5" x 5"x 0.09" Soda Lime Glass Mask, flatness <10μm	
3	4" x 4"x 0.09" Soda Lime Glass Mask, flatness <10μm	
4	User provided substrate	

## 5. Layer Information and Mask Making Instruction

Layer	 GDS No.	Field Polarity #		Dimension (μm) *		Pattern Appearance #	
name		Dark	Clear	Design	Tolerance	Normal	Mirror

# please tick one (user submitted digitized pattern is Normal Appearance)

@ please refer to Item 10 for charge rate to include user Mask Title/Label at bottom of mask.

Field Polarity:

Dark: Chrome surface





Digitized pattern

ark Field Clear Field

\* N2FC guarantee the minimum dimension and tolerance of 2.0 +/- 0.3μm. Any feature smaller than this value may not be printed correctly.

Please include clear indication (on separate sheet if necessary) on the exact location for mask dimension measurement.